



# 2012 International Workshop on EUV Lithography

Sheraton Maui Resort, Maui, Hawaii  
June 4-8, 2012

## FIRST CALL FOR PAPERS

We are inviting presentations and poster papers for the *2012 International Workshop on EUV Lithography* to be held from June 4-8, 2012, in Sheraton Maui Resort, Maui, Hawaii, USA. EUV Lithography related topics covered under this workshop are sources (HVM, Metrology and next generation), exposure tools, mask, optics, resist, contamination, metrology, patterning and cost of ownership. Technology review papers and papers with innovative approaches to address current EUV Lithography related technical challenges are encouraged.

The workshop will consist of invited papers/sessions and panel discussions, in addition to regular presentation papers and a poster session. Workshop's focus is on R & D topics and the workshop will provide a forum for discussion of current EUV Lithography technical challenges. Workshop's EUVL short course will provide participants with technical background and education in the area of EUVL. Workshop participants can expect to gain understanding of critical EUVL challenges and brainstorm innovative solutions.

On June 4, 2012 EUVL Short Course will be offered. The workshop will start with registration and a reception on June 5, 2012 and will be followed by presentations, panel discussions and poster session on June 6 and 7, 2012. The workshop will conclude with the *EUVL Workshop Steering Committee* meeting on June 8, 2012, which is also open to workshop attendees. The 2012 International Workshop on EUV Lithography is organized by EUV Litho, Inc.

### Instructions for Submissions and Deadlines

Please submit abstracts of less than 200 words. Indicate whether an oral or poster paper is preferred. Please include full name, email address, mailing address for all authors and brief biography and photograph for the presenting author, for inclusion in the abstract book. Abstracts should be submitted via email to [abstracts@euvlitho.com](mailto:abstracts@euvlitho.com).

**The deadline for abstract submission is March 2, 2012.** Abstracts will be evaluated by the workshop's technical steering committee for inclusion in the workshop. Authors will be notified by March 9, 2012, if their abstracts have been accepted for an oral or poster paper.

### Contact Information

For meeting-related issues please contact: [meeting.services@euvlitho.com](mailto:meeting.services@euvlitho.com)

For technical questions, please contact: [vivek.bakshi@euvlitho.com](mailto:vivek.bakshi@euvlitho.com)